

Kraig J. Andrews

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Education

- **Wayne State University** **Detroit, MI**
Department of Physics & Astronomy, Ph.D. Physics 2014 – Present
 - Advisor: Dr. Zhixian Zhou
 - Thesis Title: “Quantum Transport Properties and Scattering Mechanisms in Transition Metal Dichalcogenides”
 - **Wayne State University** **Detroit, MI**
Department of Physics & Astronomy, M.S. Physics 2017
 - **Michigan State University** **East Lansing, MI**
Department of Physics & Astronomy, B.S. Physics 2014
 - **Michigan State University** **East Lansing, MI**
Department of Physics & Astronomy, B.S. Astrophysics 2014
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Experience

- **Nano Fabrication & Electron Transport Laboratory** **Wayne State University, Detroit, MI**
Graduate Research Assistant 2015 – Present
 - Fabricate two-dimensional field effect transistors using transition metal dichalcogenides, such as molybdenum disulphide, tungsten diselenide, and molybdenum diselenide to investigate intrinsic transport properties.
 - Develop novel techniques for making low-resistance Ohmic contacts to a wide variety of two-dimensional semiconductors.
 - **National Institute of Materials Science** **Tsukuba, Ibaraki, Japan**
Visiting Graduate Researcher, Summer Intern 2017
 - Investigate methods for surface modification of two-dimensional semiconductors for the use of creating a highly doped contact strategy.
 - **International Course on Computational Physics** **Delft, Netherlands & East Lansing, MI**
Undergraduate Researcher 2014
 - A Joint collaboration with Technische Universiteit Delft and Michigan State University involving the development of computational models of various physical systems to model interactions of materials and optimize employed techniques.
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Core Technical Skills

Nanofabrication: Atomic force microscopy (AFM), Electron beam lithography, Photolithography, Scanning electron microscopy (SEM), General clean room abilities, Physical vapor deposition (PVD), Electron beam deposition, Plasma etching, Reactive ion etching (RIE)

Languages & Software: C++, Fortran, Java, JavaScript, L^AT_EX, Python, shell script, Microsoft Office, Matlab, Mathematica

Operating Systems: OS X, Linux OS, Microsoft Windows